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(54) **METHODS FOR MANUFACTURING A SEMICONDUCTOR DEVICE**

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H01L 29/423 (2006.01)

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(52) **U.S. Cl.**

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See application file for complete search history.

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(57)

ABSTRACT

In various embodiments, a method for manufacturing a semiconductor device is provided. The method for manufacturing a semiconductor device may include forming a first source/drain region, forming a second source/drain region, forming an active region electrically coupled between the first source/drain region and the second source/drain region, forming a trench disposed between the second source/drain region and at least a portion of the active region, forming a first isolation layer disposed over the bottom and the sidewalls of the trench, forming electrically conductive material disposed over the isolation layer in the trench, forming a second isolation layer disposed over the active region, and forming a gate region disposed over the second isolation layer. The electrically conductive material may be coupled to an electrical contact.

18 Claims, 14 Drawing Sheets

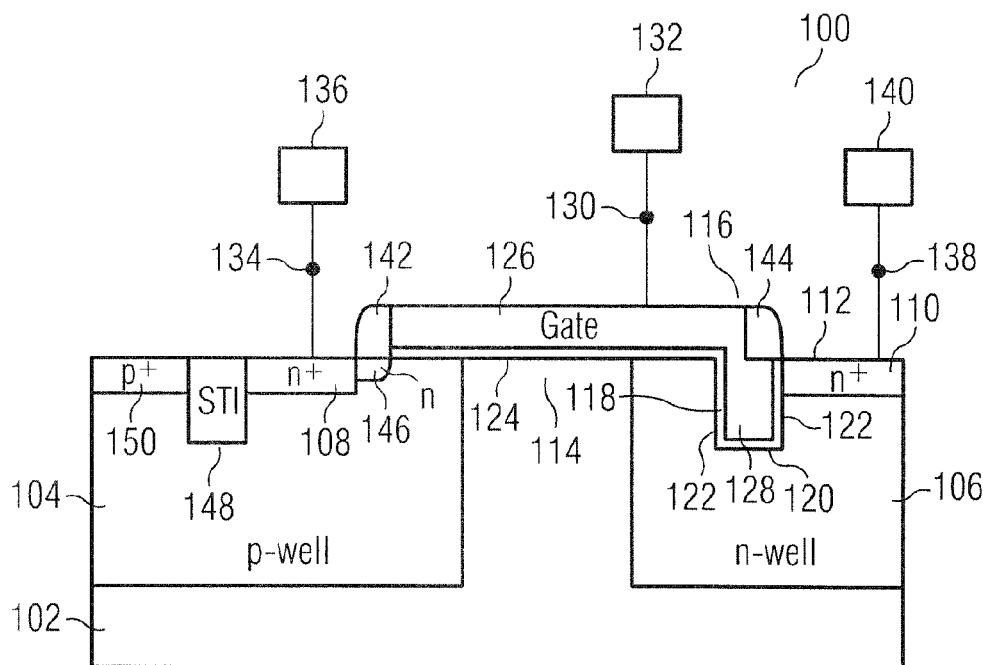
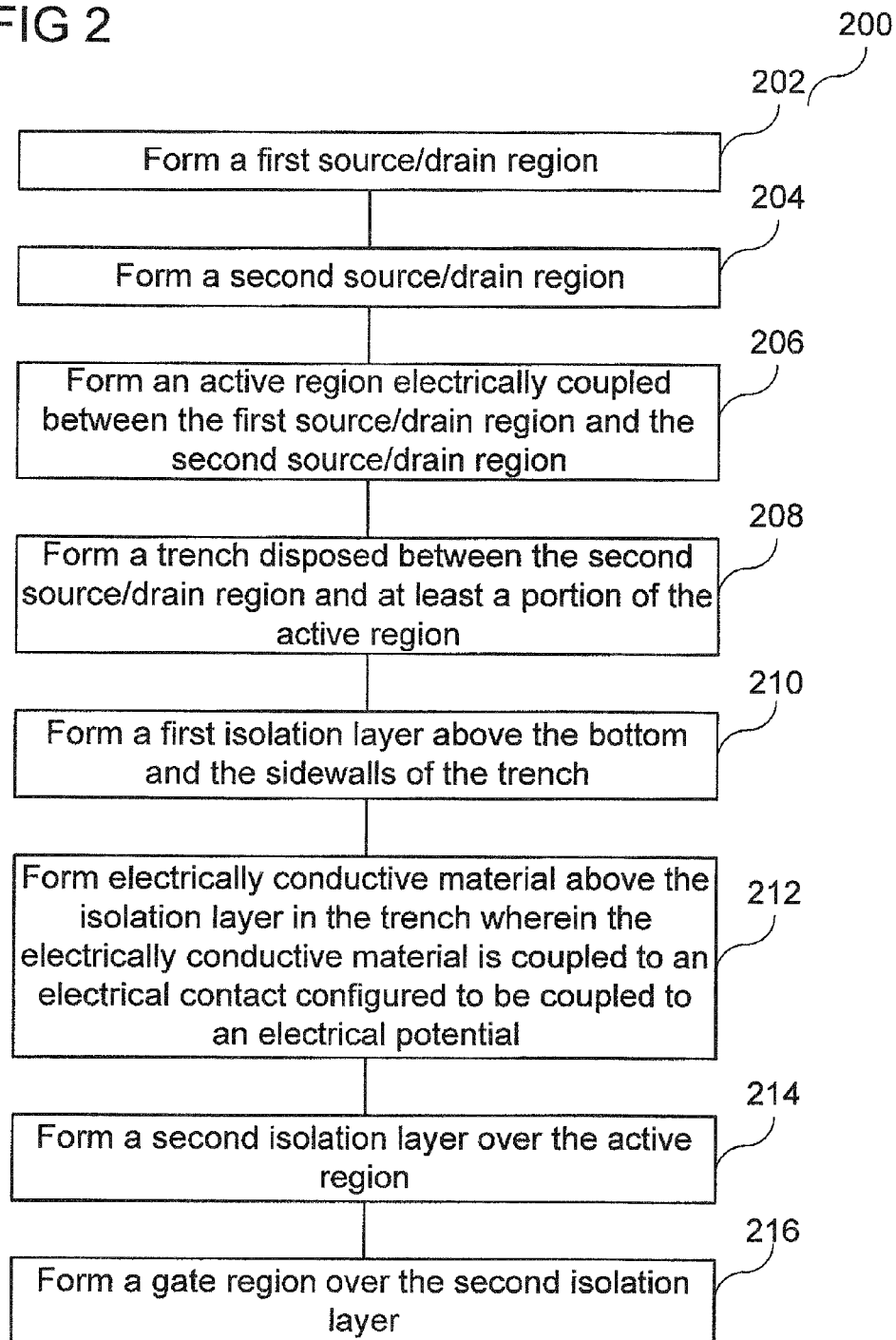


FIG 2



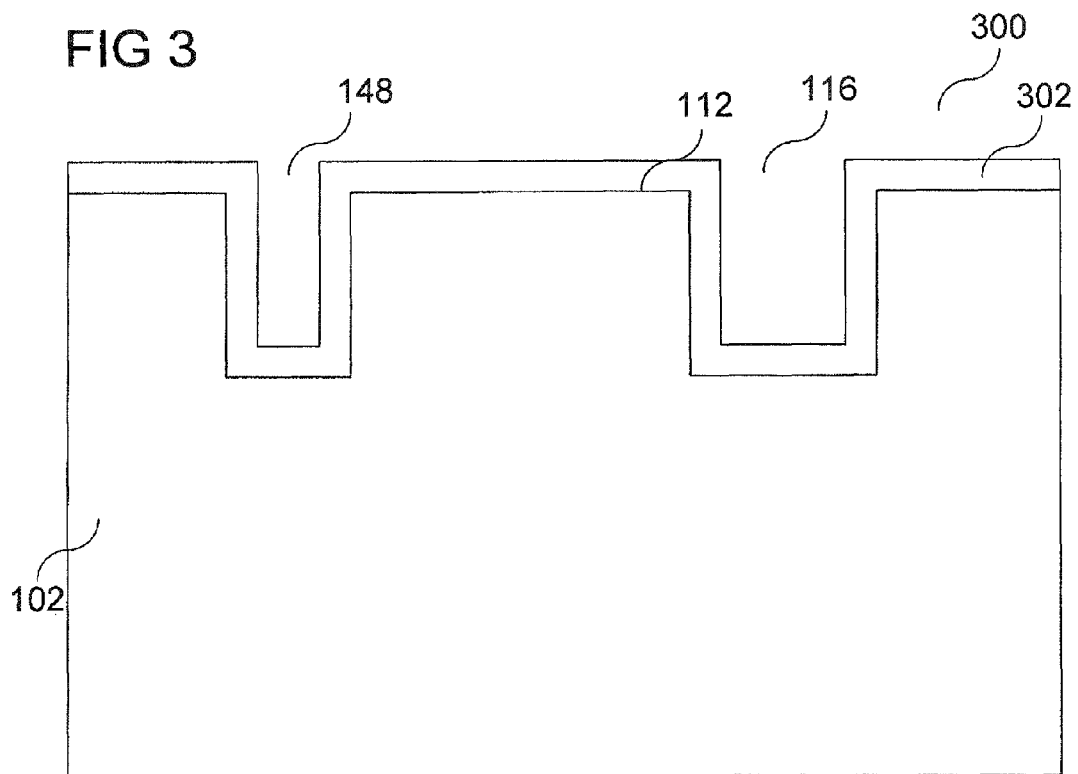


FIG 4

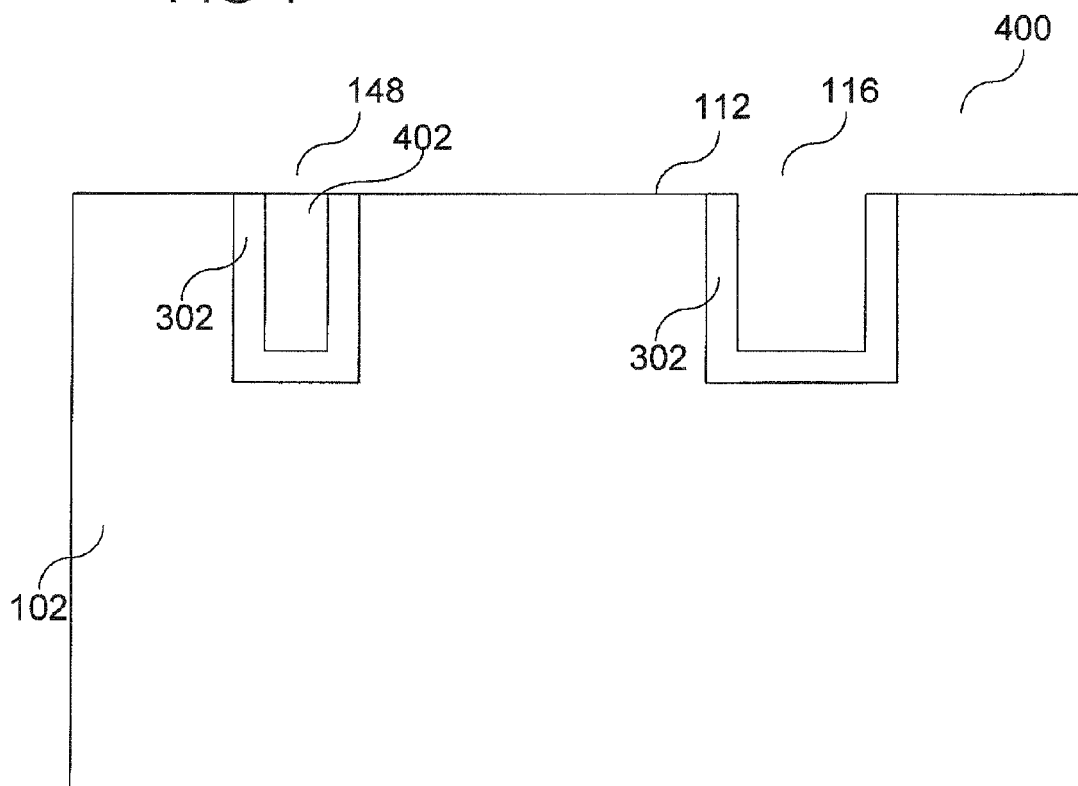


FIG 5

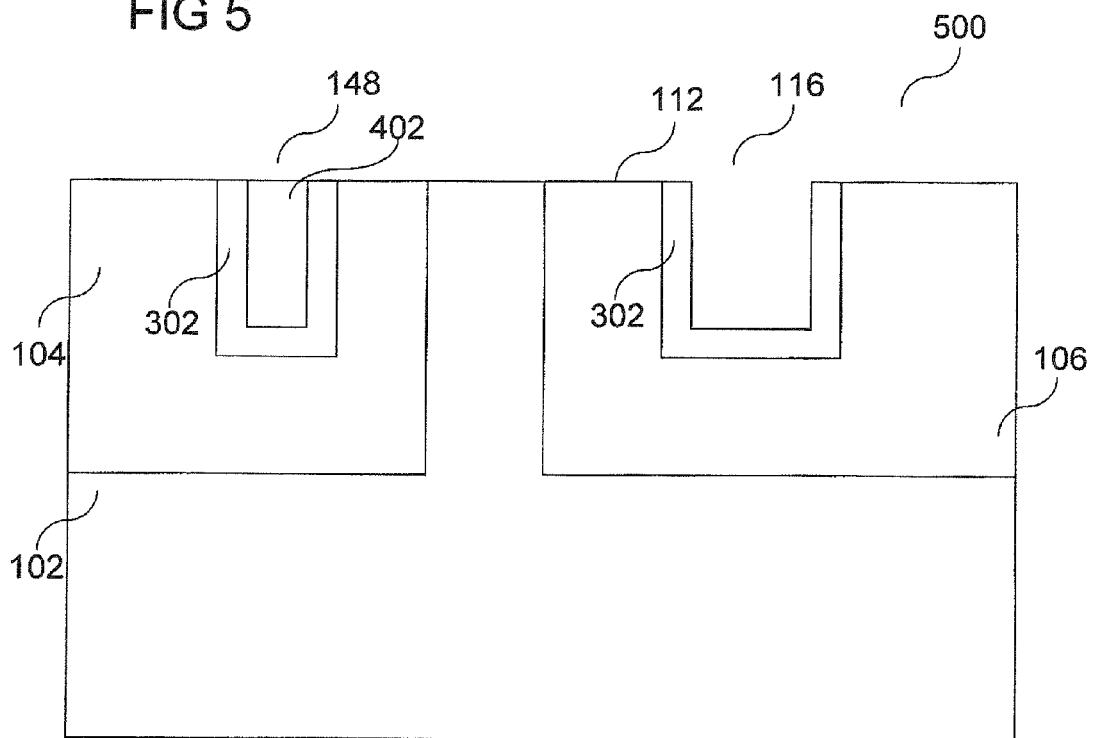


FIG 6

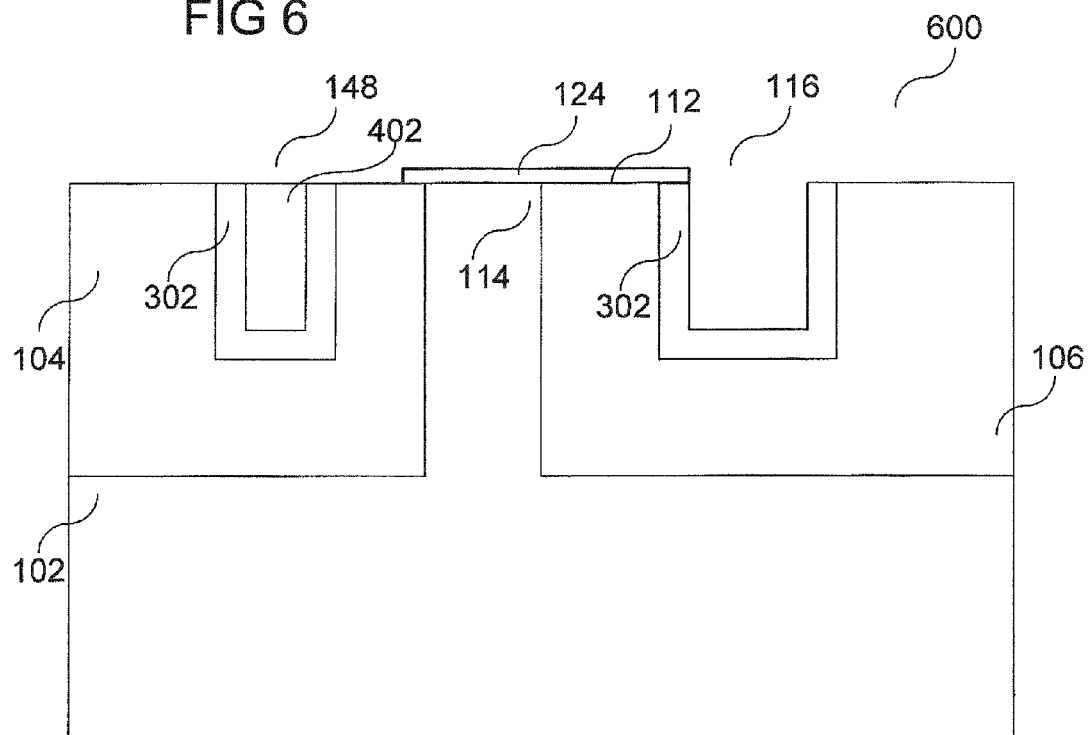


FIG 7

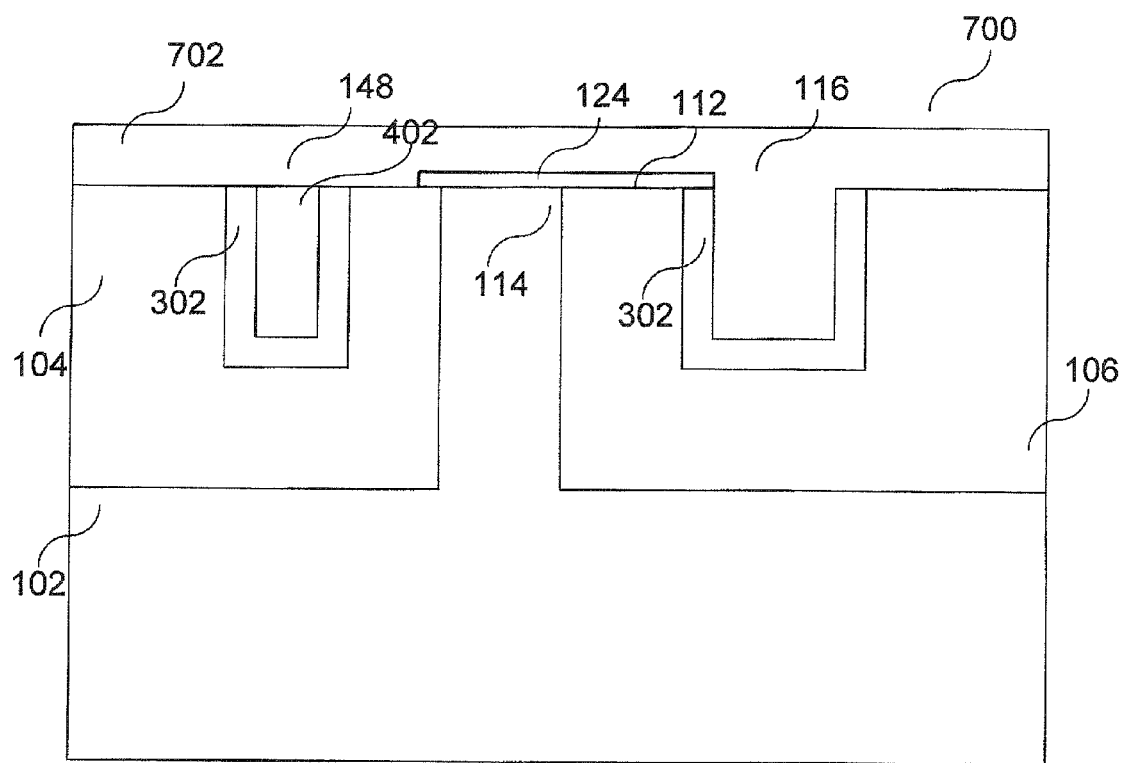


FIG 8

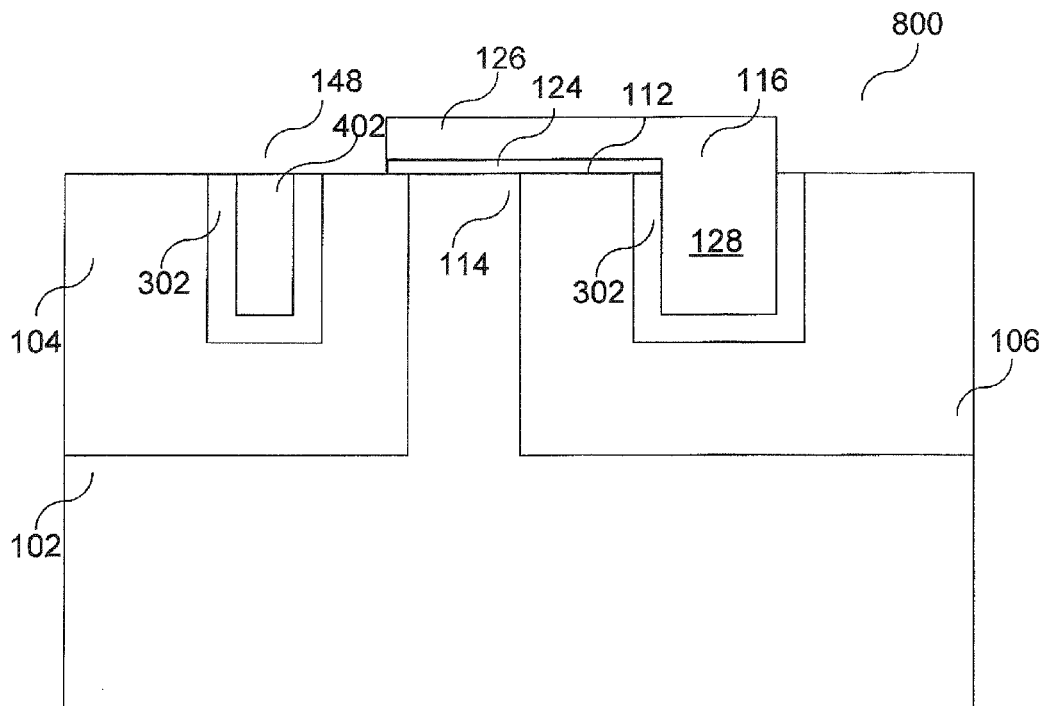


FIG 9

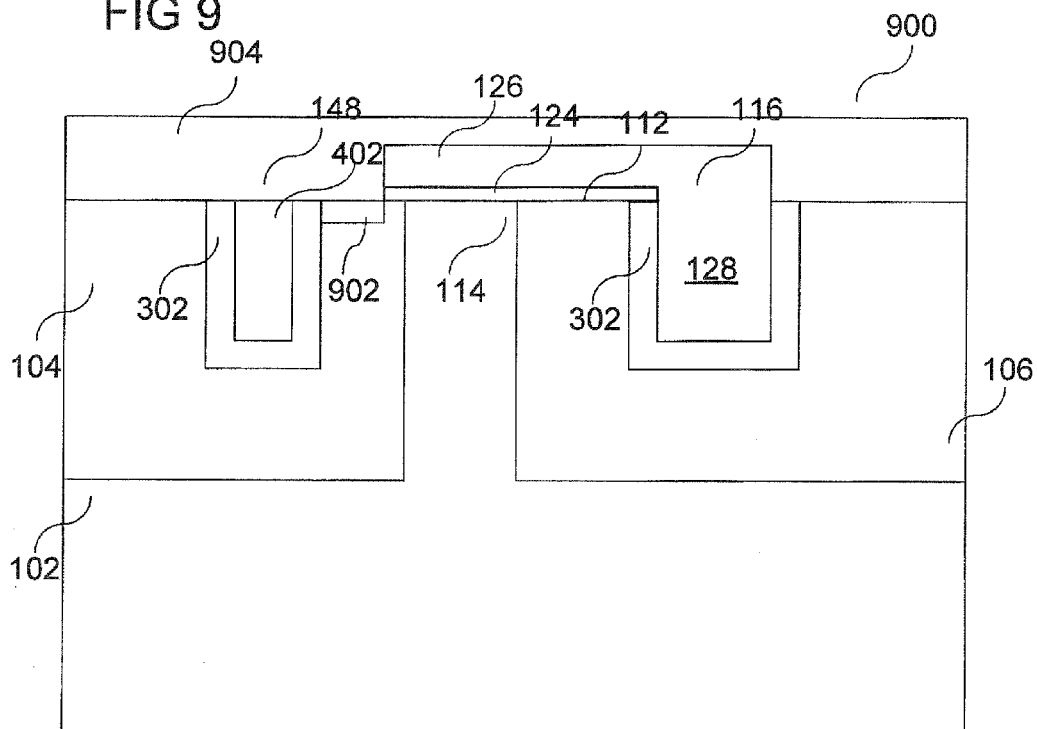


FIG 10

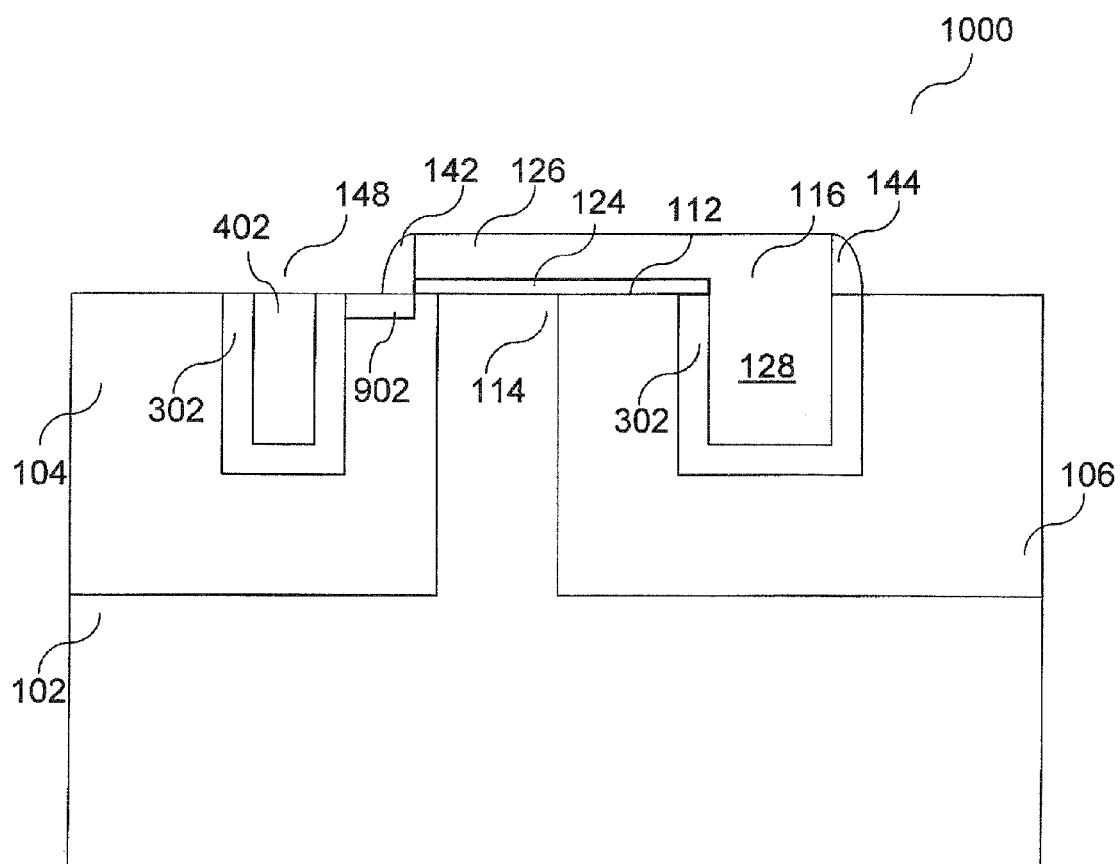


FIG 12

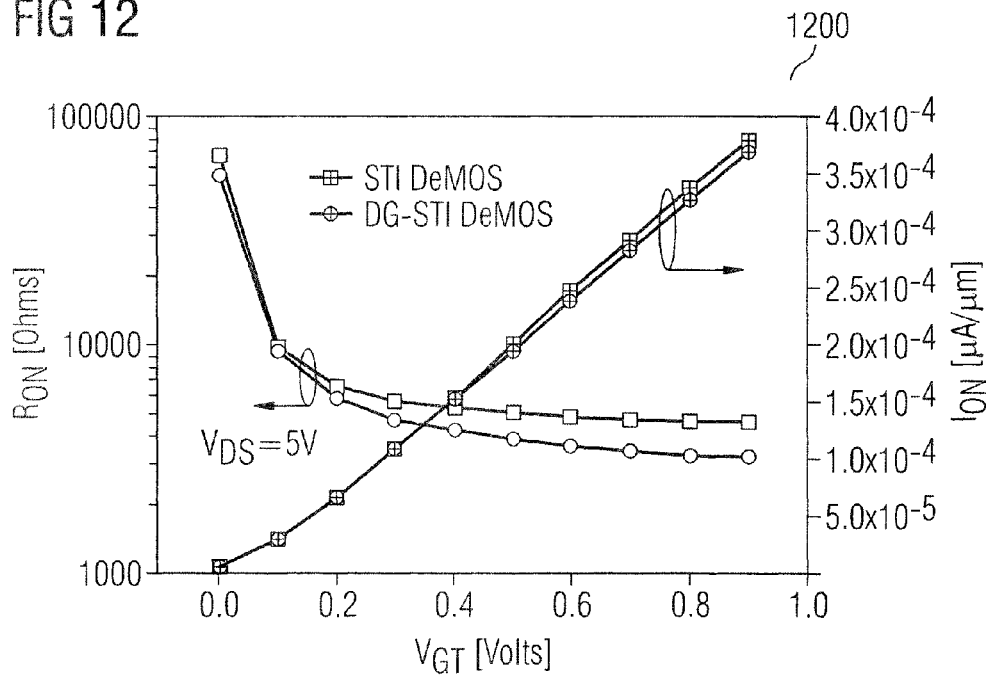


FIG 13

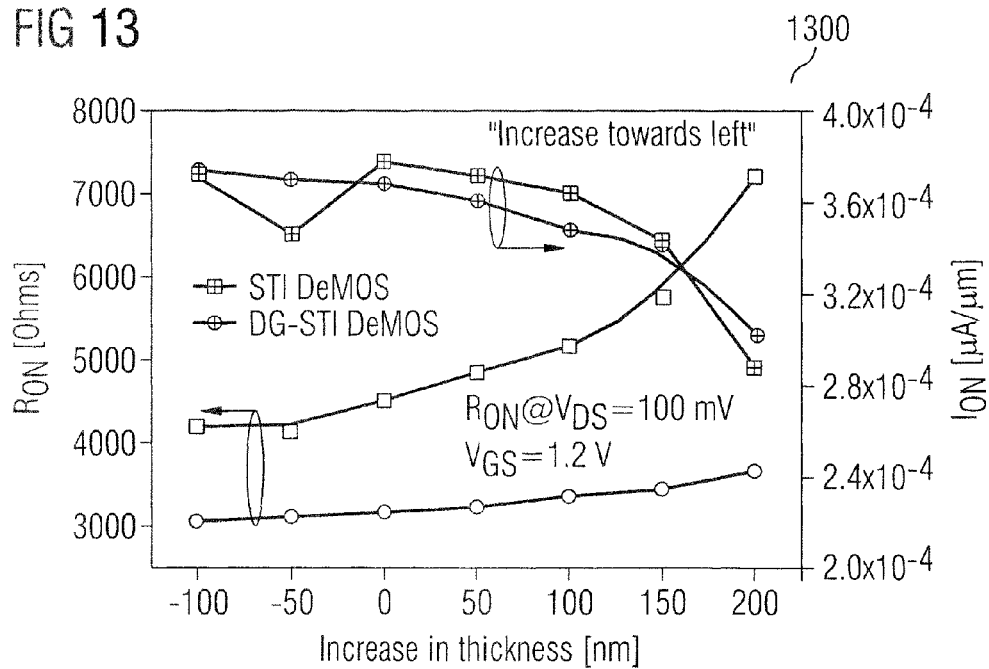
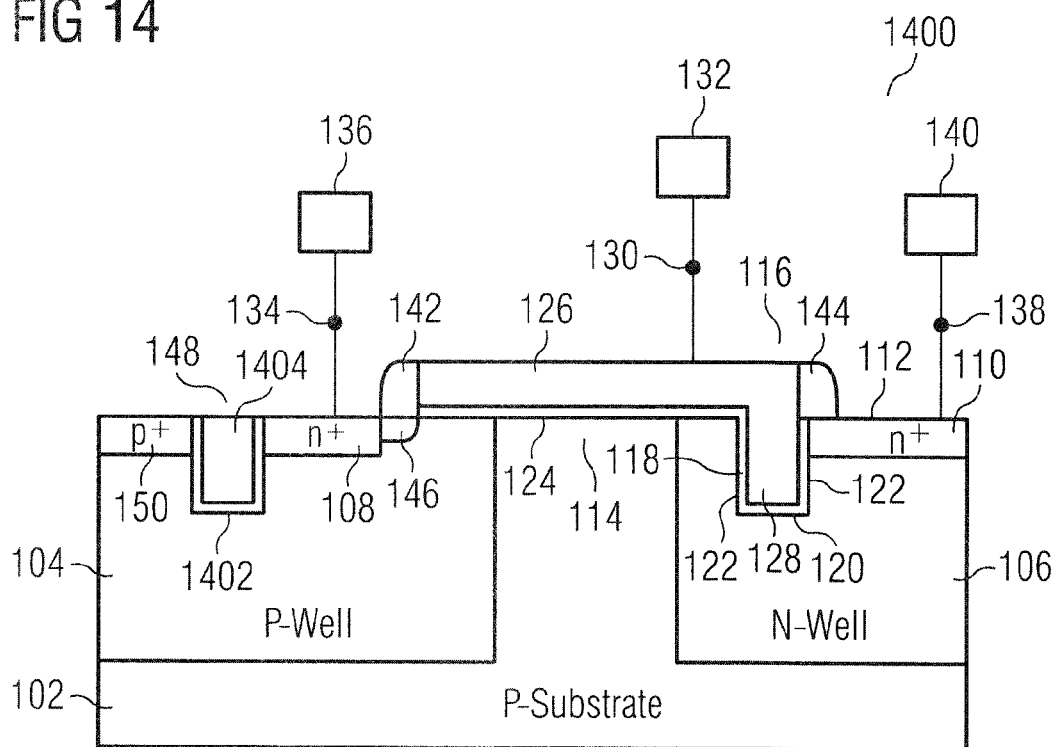
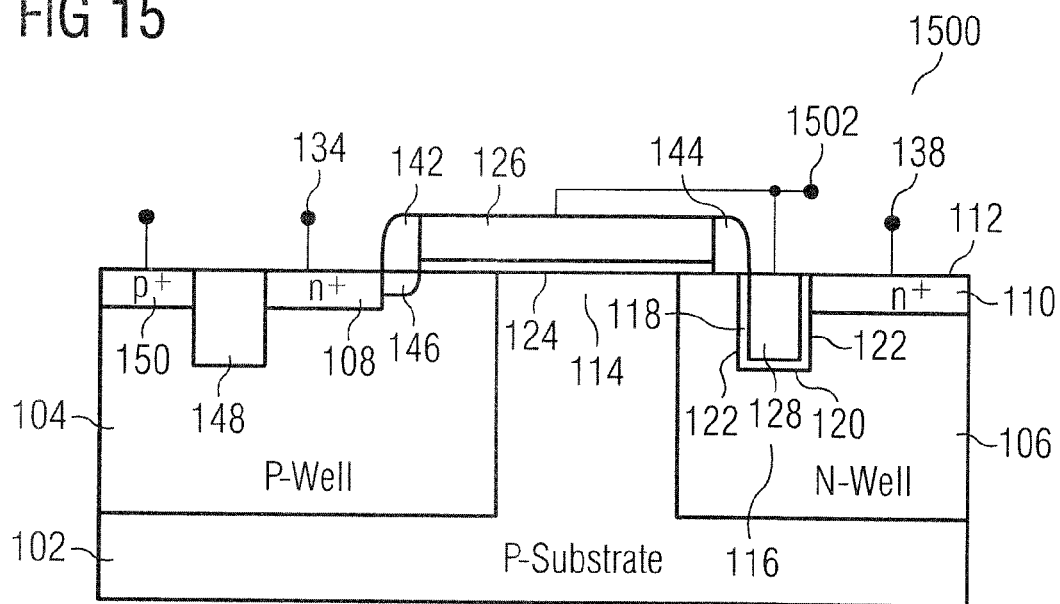


FIG 14





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METHODS FOR MANUFACTURING A SEMICONDUCTOR DEVICE

RELATED APPLICATIONS

This application is a divisional application of co-pending U.S. application Ser. No. 12/408,839, filed on Mar. 23, 2009, the entire content of which is hereby incorporated by reference.

TECHNICAL FIELD

Embodiments relate generally to semiconductor devices and to methods for manufacturing a semiconductor device.

BACKGROUND

A so-called Lightly-Doped Drain Metal Oxide Semiconductor (LDDMOS) (RESURF) device is currently in use for Input/Output (I/O) or high voltage applications. At scaled technology nodes, high drain resistance because of the presence of an LDD region (which is used to increase the breakdown voltage), degrades its mixed signal performance and also it may have high hot carrier degradation. To achieve higher breakdown voltage with improved mixed signal performance, a Drain extended MOS device may be used (DeMOS), but this device usually shows very high hot carrier degradation and high electrical field in the gate oxide. To reduce the electrical field in the gate oxide, a shallow trench isolation (STI) may conventionally be realized underneath the gate-to-drain-overlap using a standard STI process. This new STI DeMOS device, however, usually has an even worse mixed signal performance as compared to the previously mentioned devices.

BRIEF DESCRIPTION OF THE DRAWINGS

In the drawings, like reference characters generally refer to the same parts throughout the different views. The drawings are not necessarily to scale, emphasis instead generally being placed upon illustrating the principles of various embodiments. In the following description, various embodiments are described with reference to the following drawings, in which:

FIG. 1 shows a cross sectional view of a semiconductor device in accordance with an embodiment;

FIG. 2 shows a flow diagram illustrating a method for manufacturing a semiconductor device in accordance with an embodiment;

FIG. 3 shows a cross sectional view of a semiconductor device in accordance with an embodiment at a first stage of its manufacturing;

FIG. 4 shows a cross sectional view of a semiconductor device in accordance with an embodiment at a second stage of its manufacturing;

FIG. 5 shows a cross sectional view of a semiconductor device in accordance with an embodiment at a third stage of its manufacturing;

FIG. 6 shows a cross sectional view of a semiconductor device in accordance with an embodiment at a fourth stage of its manufacturing;

FIG. 7 shows a cross sectional view of a semiconductor device in accordance with an embodiment at a fifth stage of its manufacturing;

FIG. 8 shows a cross sectional view of a semiconductor device in accordance with an embodiment at a sixth stage of its manufacturing;

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FIG. 9 shows a cross sectional view of a semiconductor device in accordance with an embodiment at a seventh stage of its manufacturing;

FIG. 10 shows a cross sectional view of a semiconductor device in accordance with an embodiment at an eighth stage of its manufacturing;

FIG. 11 shows a cross sectional view of a semiconductor device in accordance with an embodiment at a ninth stage of its manufacturing;

FIG. 12 shows a diagram illustrating the On-resistance and the On-current dependent from the applied gate voltage of the semiconductor device of FIG. 1;

FIG. 13 shows a diagram illustrating the On-resistance and the On-current dependent from the thickness of the insulating layer within the first trench of the semiconductor device of FIG. 1;

FIG. 14 shows a cross sectional view of a semiconductor device in accordance with another embodiment; and

FIG. 15 shows a cross sectional view of a semiconductor device in accordance with yet another embodiment.

DESCRIPTION

The following detailed description refers to the accompanying drawings that show, by way of illustration, specific details and embodiments in which the invention may be practiced. These embodiments are described in sufficient detail to enable those skilled in the art to practice the invention. Other embodiments may be utilized and structural, logical, and electrical changes may be made without departing from the scope of the invention. The various embodiments are not necessarily mutually exclusive, as some embodiments can be combined with one or more other embodiments to form new embodiments.

Various embodiments provide a semiconductor device, e.g. a drain extended Metal Oxide Semiconductor (MOS) device with sufficient dielectric reliability and hot carrier reliability and with only little or even without degraded mixed signal performance at high voltage Input/Output (I/O) interfaces in scaled Complementary Metal Oxide Semiconductor (CMOS) technologies. The extended drain region may be provided to reduce the voltage at the thin gate oxide.

As will be described in more detail below, in various embodiments, a drain extended metal oxide semiconductor (DeMOS) device and a dual gate process to manufacture the same is provided, which may improve the turn-on property without affecting gate dielectric reliability and hot charge carrier reliability.

FIG. 1 shows a cross sectional view of a semiconductor device **100**, e.g. implemented as a DeMOS semiconductor device **100**, in accordance with an embodiment.

As shown in FIG. 1, the semiconductor device **100** may include a substrate **102**, e.g. a p-doped substrate, e.g. a silicon substrate, e.g. a p-doped silicon substrate (e.g. having a doping concentration of p-doping atoms (such as e.g. Boron (B) atoms) in the range from about 10^{14} cm^{-3} to about 10^{17} cm^{-3} , e.g. in the range from about 10^{15} cm^{-3} to about 10^{16} cm^{-3}) in the case of an re-channel field effect semiconductor device **100**. In the case of a p-channel field effect semiconductor device **100**, an n-doped well region (not shown) may be provided in which the p-channel field effect semiconductor device **100** might be located. The n-doped well region may be doped with n-doping atoms (such as e.g. Arsenic (As) or Phosphorous (P)) in the range from about 10^{15} cm^{-3} to about 10^{19} cm^{-3} , e.g. in the range from about 10^{17} cm^{-3} to about 10^{18} cm^{-3}).

Although the elements described below with reference to FIG. 1 refer to an n-channel semiconductor device, the respective conductivity type of the doped regions may simply be inverted to provide a p-channel semiconductor device.

The semiconductor device **100** may further include a first well region **104**, e.g. being p-doped (e.g. having a well doping concentration of p-doping atoms (such as e.g. Boron (B) atoms) in the range from about 10^{16} cm^{-3} to about 10^{19} cm^{-3} , e.g. in the range from about $5 \cdot 10^{16} \text{ cm}^{-3}$ to about $5 \cdot 10^{18} \text{ cm}^{-3}$, e.g. about 10^{17} cm^{-3} .

Furthermore, the semiconductor device **100** may further include a second well region **106**, e.g. being n-doped (e.g. having a well doping concentration of n-doping atoms (such as e.g. Arsenic (As) or Phosphorous (P)) in the range from about 10^{16} cm^{-3} to about 10^{19} cm^{-3} , e.g. in the range from about $5 \cdot 10^{16} \text{ cm}^{-3}$ to about $5 \cdot 10^{18} \text{ cm}^{-3}$, e.g. about 10^{17} cm^{-3} . The second well region **106** may be laterally disposed from the first well region **104**. In an alternative embodiment, the first well region **104** may laterally extend below the gate stack (which will be described in more detail below) to the second well region **106** such that it is arranged immediately adjacent to the second well region **106**.

In various embodiments, a first source/drain region **108** (e.g. a source region **108**) may be provided in the first well region **104**, wherein the first source/drain region **108** may be highly n-doped (n^+ doped) having a doping concentration in the range from about 10^{19} cm^{-3} to about 10^{21} cm^{-3} , e.g. with a doping concentration of doping atoms in the range from about $5 \cdot 10^{19} \text{ cm}^{-3}$ to about $5 \cdot 10^{20} \text{ cm}^{-3}$. In general, the first source/drain region **108** may be doped with doping atoms of a first conductivity type, and the first well region **104** may be doped with doping atoms of a second conductivity type, wherein the second conductivity type is different from the first conductivity type.

Furthermore, in various embodiments, a second source/drain region **110** (e.g. a drain region **110**) may be provided in the second well region **106**, wherein the second source/drain region **110** may be highly n-doped (n^+ doped) having a doping concentration in the range from about 10^{19} cm^{-3} to about 10^{21} cm^{-3} , e.g. with a doping concentration of doping atoms in the range from about $5 \cdot 10^{19} \text{ cm}^{-3}$ to about $5 \cdot 10^{20} \text{ cm}^{-3}$. In general, the second source/drain region **110** may be doped with doping atoms of the first conductivity type, and the second well region **106** may be doped with doping atoms of the first conductivity type as well.

In various embodiments, the first source/drain region **108** as well as the second source/drain region **110** may extend into the substrate **102** from the upper main processing surface **112** of the substrate **102** by a depth in the range from about 50 nm to about 200 nm, wherein the depth of the first source/drain region **108** and the depth of the second source/drain region **110** may be similar or different from each other.

An active region **114** (which may also be referred to as a body region **112**) may also be provided electrically coupled between the first source/drain region **108** and the second source/drain region **110**. The active region **114** may be understood as being a region which may be rendered electrically conductive (in other words form a conductive channel) in response to an appropriate voltage application to a gate region (which will be described in more detail below) and to the first source/drain region **108** and the second source/drain region **110**. In an embodiment, the active region **114** laterally extends from the first source/drain region **108** to the second source/drain region **110** and may include a portion of the first well region **104** and a portion of the second well region **106**.

In various embodiments, a trench **116** may be disposed between the second source/drain region **110** and at least a

portion of the active region **114**. In various embodiments, the trench **116** may extend into the substrate **102** from the upper main processing surface **112** of the substrate **102** by a depth in the range from about 300 nm to about 400 nm. In various embodiments, the trench **116** may have a width in the range from about 200 nm to about 1000 nm. Thus, illustratively, in various embodiments, the trench **116** may be understood as a shallow trench isolation structure partially filled with electrically conductive material.

In various embodiments, a first isolation layer **118** may be disposed over the bottom **120** and the sidewalls **122** of the trench **116**. The first isolation layer **118** may include or consist of a dielectric material such as e.g. an oxide (e.g. silicon oxide), a nitride (e.g. silicon nitride) or an oxynitride (ON). In alternative embodiments, the first isolation layer **118** may include or consist of high k dielectric material (i.e. e.g. a material having a dielectric constant of greater than the dielectric constant of silicon oxide (which has a dielectric constant of 3.9)). In various implementations, the first isolation layer **118** may include or consist of may include or consist of aluminum oxide (Al_2O_3), yttrium oxide (Y_2O_3), hafnium oxide (HfO_2), lanthanum oxide (LaO_2), zirconium oxide (ZrO_2), amorphous silicon (a-Si), tantalum oxide (Ta_2O_5), titanium oxide (TiO_2), and/or an aluminate. An example for an aluminate is an alloy of the components aluminum, zirconium and oxygen (AlZrO). In an implementation, the first isolation layer **118** may include or consist of a dielectric layer stack including three dielectric layers being formed above one another, e.g. a first oxide layer (e.g. silicon oxide), a nitride layer as charge trapping layer (e.g. silicon nitride) on the first oxide layer, and a second oxide layer (e.g. silicon oxide or aluminum oxide) on the nitride layer. This type of dielectric layer stack is also referred to as ONO layer stack. In an alternative implementation, the first isolation layer **118** may include or consist of two, four or even more dielectric layers being formed above one another. In some embodiments, the first isolation layer **118** may cover the entire bottom **120** and the entire sidewalls **122** of the trench **116**.

In various embodiments, a second isolation layer **124** (e.g. a gate dielectric layer **124**) may be disposed over the active region **114**. The second isolation layer **124** may include or consist of a dielectric material such as e.g. an oxide (e.g. silicon oxide), a nitride (e.g. silicon nitride) or an oxynitride (ON). In alternative embodiments, the second isolation layer **124** may include or consist of high k dielectric material (i.e. e.g. a material having a dielectric constant of greater than the dielectric constant of silicon oxide (which has a dielectric constant of 3.9)). In various implementations, the second isolation layer **124** may include or consist of may include or consist of aluminum oxide (Al_2O_3), yttrium oxide (Y_2O_3), hafnium oxide (HfO_2), lanthanum oxide (LaO_2), zirconium oxide (ZrO_2), amorphous silicon (a-Si), tantalum oxide (Ta_2O_5), titanium oxide (TiO_2), and/or an aluminate. An example for an aluminate is an alloy of the components aluminum, zirconium and oxygen (AlZrO). In an implementation, the second isolation layer **124** may include or consist of a dielectric layer stack including three dielectric layers being formed above one another, e.g. a first oxide layer (e.g. silicon oxide), a nitride layer as charge trapping layer (e.g. silicon nitride) on the first oxide layer, and a second oxide layer (e.g. silicon oxide or aluminum oxide) on the nitride layer. This type of dielectric layer stack is also referred to as ONO layer stack. In an alternative implementation, the second isolation layer **124** may include or consist of two, four or even more dielectric layers being formed above one another. In some embodiments, the second isolation layer **124** may have a

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physical layer thickness in the range from about 1.5 nm to about 5 nm, e.g. a physical layer thickness in the range from about 2 nm to about 3 nm and/or an equivalent oxide thickness (EOT) in the range from about 1 nm to about 2 nm.

In some embodiments, the first isolation layer **118** and the second isolation layer **124** may be made of the same material and may optionally be formed as one common layer or layer structure.

Furthermore, in various embodiments, a gate region **126** may be disposed over the second isolation layer **124**. In some embodiments, the gate region **126** may include or consist of electrically conductive material such as e.g. polysilicon (doped or undoped) or a metal such as tungsten or a silicide (e.g. WSi).

Moreover, the trench **116** may be filled with electrically conductive material **128**. In other words, electrically conductive material **128** may be disposed over the first isolation layer **118** in the trench **116**. In some embodiments, the electrically conductive material **128** may be the same material as the material of the gate region **126**. In an alternative embodiment, the electrically conductive material **128** and the material of the gate region **126** may be different materials. In various embodiments, as will be described in more detail below, the electrically conductive material **128** and the material of the gate region **126** may be deposited in the same deposition process. As shown in FIG. 1, the electrically conductive material **128** and the material of the gate region **126** may be in direct physical contact and/or may be electrically coupled with each other. In general, in various embodiments, the electrically conductive material **128** is coupled to an electrical contact **130** (e.g. via the gate region **126** e.g. to a gate terminal **130** or to a separate individual electrical terminal or contact) configured to be coupled to an electrical potential, e.g. by means of a gate voltage source **132** coupled to the gate terminal **130**. As shown in FIG. 10, in various embodiments, the material of the gate region **126** and the electrically conductive material **128** may be provided in one common layer, in other words, in one piece. Furthermore, in various embodiments, the material of the gate region **126** and the electrically conductive material **128** may be commonly produced in one common process or more common processes.

In various embodiments, the first source/drain region **108** and/or the second source/drain region **110** may include or consist of a silicide. Furthermore, the first source/drain region **108** may be connected to a first source/drain terminal (e.g. a source terminal) **134** and may be coupled to an electrical potential, e.g. by means of a first source/drain voltage source **136** coupled to the first source/drain terminal **134**. The second source/drain region **110** may be connected to a second source/drain terminal (e.g. a drain terminal) **138** and may be coupled to an electrical potential, e.g. by means of a second source/drain voltage source **140** coupled to the second source/drain terminal **138**.

As shown in FIG. 1, optionally, gate sidewall spacers **142**, **144** (e.g. including or consisting of electrically isolating material such as e.g. an oxide (e.g. silicon oxide) or a nitride (e.g. silicon nitride)) may be provided at the sidewalls of and adjacent to the gate region **126**. Furthermore, in various embodiments, the semiconductor device **100** may further include a lightly doped drain region **146** disposed between the first source/drain region **146** and the active region **114**. The lightly doped drain region **146** may be disposed below the first gate sidewall spacer **142** and may be doped with n-doping atoms (such as e.g. Arsenic (As) or Phosphorous (P)) e.g. with a doping concentration in the range from about 10^{17} cm⁻³ to about 10^{19} cm⁻³, e.g. in the range from about 10^{17} cm⁻³ to about 10^{18} cm⁻³.

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Furthermore, in various embodiments, the semiconductor device **100** may further include a further trench **148** disposed next to the first source/drain region **108** opposite to the active region **114**. The further trench **148** may have a similar depth or a different depth compared with the trench **116**. The further trench **148** may be completely filled with an electrically insulating material such as a dielectric, e.g. an oxide (e.g. silicon oxide) or a nitride (e.g. silicon nitride). The further trench **148** may be a shallow trench isolation (STI).

In some embodiments, the electrically conductive material **128** in the trench **116** may act like an electrical isolation in the OFF-state of the semiconductor device **100** and may help in maintaining gate oxide reliability and hot carrier reliability. Furthermore, in some embodiments, it may reduce the on-resistance R_{ON} in the ON-state of the semiconductor device **100** and may improve the mixed signal performance as compared e.g. to a standard STI DeMOS semiconductor device fabricated at same technology node.

Various embodiments may be based on a dual STI process and may provide one or more of the following effects:

Various embodiments may be useful for scaled technology nodes.

Various embodiments may provide improved gate oxide reliability and hot carrier reliability as compared to a LDDMOS semiconductor device and a DeMOS semiconductor device.

Various embodiments may provide improved mixed signal performance.

Various embodiments may provide improved variability.

Various embodiments may provide a high breakdown voltage.

Various embodiments may save two masks steps, e.g. the so-called LDD implantation mask and e.g. the so-called silicide blocking mask compared with the conventional LDDMOS process flow.

Various embodiments relate to a method to achieve improved turn-on behaviour and mixed signal performance of a Drain extended MOS device having high breakdown (higher than LDDMOS in the same technology node) with improved gate dielectric reliability and hot carrier reliability.

As shown in FIG. 1, a further doped region **150** (e.g. highly p-doped region) may be disposed next to the further trench **148** opposite to the first source/drain region **108**.

FIG. 2 shows a flow diagram **200** illustrating a method for manufacturing a semiconductor device in accordance with an embodiment. The method may include, in **202**, forming a first source/drain region, and, in **204**, forming a second source/drain region. The method may further include, in **206**, forming an active region electrically coupled between the first source/drain region and the second source/drain region. The method may further include, in **208**, forming a trench disposed between the second source/drain region and at least a portion of the active region. Furthermore, in **210**, a first isolation layer may be formed above the bottom and the sidewalls of the trench, and, in **212**, electrically conductive material may be formed over the isolation layer in the trench, wherein the electrically conductive material is coupled to an electrical contact configured to be coupled to an electrical potential. In **214**, a second isolation layer may be formed over the active region, and, in **216**, a gate region may be formed over the second isolation layer.

In an implementation of this embodiment, the method may further include forming a first well region, wherein the first source/drain region is formed within the first well region. In another implementation of this embodiment, the first source/drain region may be doped with doping atoms of a first conductivity type, and the first well region may be doped with

doping atoms of a second conductivity type, wherein the second conductivity type is different from the first conductivity type. In yet another implementation of this embodiment, the method may further include forming a second well region, wherein the second source/drain region is formed within the second well region. In yet another implementation of this embodiment, the second source/drain region may be doped with doping atoms of a first conductivity type, and the second well region may be doped with doping atoms of the first conductivity type. In yet another implementation of this embodiment, the method may further include forming a lightly doped drain region between the first source/drain region and the active region. In yet another implementation of this embodiment, the first isolation layers may include or consist of at least one of the following materials consisting of: silicon oxide; silicon nitride high-k material. In yet another implementation of this embodiment, the second isolation layers may include or consist of at least one of the following materials: silicon oxide; silicon nitride high-k material. In yet another implementation of this embodiment, at least one of the first source/drain region and the second source/drain region may include or consist of silicide. In yet another implementation of this embodiment, the trench may be formed as a shallow trench isolation structure. In yet another implementation of this embodiment, the gate region may be electrically coupled with the electrically conductive material. In yet another implementation of this embodiment, the electrically conductive material may include or consist of a metal. In yet another implementation of this embodiment, the metal may include or consist of tungsten or a silicide (e.g. WSi). In yet another implementation of this embodiment, the method may further include forming a further trench disposed next to the first source/drain region opposite to the active region. In yet another implementation of this embodiment, the further trench may be formed as a shallow trench isolation structure.

The process illustrated below needs one additional masking step at the initial stage of the semiconductor device fabrication to plug-out the oxide from the trench, as will be described in more detail below.

FIG. 3 shows a cross sectional view **300** of a semiconductor device in accordance with an embodiment at a first stage of its manufacturing. Although the elements described below with reference to the manufacturing process refer to an n-channel semiconductor device, the respective conductivity type of the doped regions may simply be inverted to provide a p-channel semiconductor device.

As shown in FIG. 3, a substrate **102**, e.g. a p-doped substrate, e.g. a silicon substrate, e.g. a p-doped silicon substrate (e.g. having a doping concentration of p-doping atoms (such as e.g. Boron (B) atoms) in the range from about 10^{14} cm^{-3} to about

10^{17} cm^{-3} , e.g. in the range from about 10^{15} cm^{-3} to about 10^{16} cm^{-3}) in the case of an n-channel field effect semiconductor device **100**, may be provided. In the case of a p-channel field effect semiconductor device **100**, an n-doped well region (not shown) may be provided in which the p-channel field effect semiconductor device **100** might be located. The n-doped well region may be doped with n-doping atoms (such as e.g. Arsenic (As) or Phosphorous (P)) in the range from about 10^{15} cm^{-3} to about

10^{19} cm^{-3} , e.g. in the range from about 10^{17} cm^{-3} to about 10^{18} cm^{-3}). A first trench **116** and a second trench **148** may be formed into the substrate **102**, e.g. by means of an etching process, e.g. by means of an anisotropic etching process such as e.g. a reactive ion etching (RIE) process. The first trench **116** and the second trench **148** may be laterally disposed from each other. In various embodiments, the first trench **116** may

extend into the substrate **102** from the upper main processing surface **112** of the substrate **102** by a depth in the range from about 300 nm to about 400 nm. In various embodiments, the trench **116** may have a width in the range from about 200 nm to about 1000 nm. Thus, illustratively, in various embodiments, the trench **116** may be understood as a shallow trench isolation structure partially filled with electrically conductive material. The second trench **148** may have a similar depth or a different depth compared with the first trench **116**. Furthermore, a liner layer **302**, e.g. comprising of consisting of an electrically isolating material such as e.g. a nitride, e.g. silicon nitride, may be deposited over the entire exposed upper surface of the substrate **102**, the bottom and the sidewall surfaces of the first trench **116** and the second trench **148**. In an embodiment, the liner layer **302** may be formed to have a layer thickness in the range from about 4 nm to about 20 nm, e.g. to have a layer thickness in the range from about 5 nm to about 10 nm. It is to be noted that in some embodiments, the liner layer **302** in the first trench **116** may be an implementation of the first isolation layer.

FIG. 4 shows a cross sectional view **400** of a semiconductor device in accordance with an embodiment at a second stage of its manufacturing.

Then, as shown in FIG. 4, portions of the liner layer **302** are removed from the upper main processing surface **112** of the substrate **102**, whereas the portions of the liner layer covering the bottom and the sidewall surfaces of the first trench **116** and the second trench **148** remain. The removal of the portions of the liner layer **302** from the upper main processing surface **112** of the substrate **102** may be carried out by means of a polishing process, e.g. by means of a chemical mechanical polishing (CMP). Furthermore, the first trench **116** and the second trench **148** may be filled (and possibly overfilled) with an electrically isolating material **402** such as e.g. an oxide (e.g. silicon oxide). In an embodiment, the electrically isolating material **402** overfilling the trenches **116**, **148** may be removed, e.g. using a CMP process. It is to be noted that the process flow may be different in an alternative embodiment, in which the removal of the liner layer **302** from the upper main processing surface **112** of the substrate **102** may be carried out after the deposition of the electrically isolating material **402**. Furthermore, as shown in FIG. 4, in another process, the electrically isolating material **402** may be removed again (e.g. plugged out) from the first trench **116**, so that only the second trench **148** remains filled with the electrically isolating material **402**. In various embodiments, the removal of the electrically isolating material **402** from the first trench **116** may be carried out e.g. using an extra mask to e.g. etch the electrically isolating material **402** out of the first trench **116**, which will later be used underneath the gate-to-drain overlap.

FIG. 5 shows a cross sectional view **500** of a semiconductor device in accordance with an embodiment at a third stage of its manufacturing.

Then, as shown in FIG. 5, well implant processes may be provided to form the first well region **104** and the second well region **106**. It should be mentioned that the well formation processes may be carried out before the removal (e.g. etching) of the electrically isolating material **402** from the first trench **116**.

By way of example, the first well region **104** may be formed, e.g. to be p-doped (e.g. having a well doping concentration of p-doping atoms (such as e.g. Boron (B) atoms) in the range from about 10^{16} cm^{-3} to about 10^{19} cm^{-3} , e.g. in the range from about $5 \cdot 10^{16} \text{ cm}^{-3}$ to about $5 \cdot 10^{18} \text{ cm}^{-3}$, e.g. about 10^{17} cm^{-3} . Furthermore, the second well region **106** may be formed, e.g. to be n-doped (e.g. having a well doping

concentration of n-doping atoms (such as e.g. Arsenic (As) or Phosphorous (P)) in the range from about 10^{16} cm^{-3} to about 10^{19} cm^{-3} , e.g. in the range from about $5 \cdot 10^{16} \text{ cm}^{-3}$ to about $5 \cdot 10^{18} \text{ cm}^{-3}$, e.g. about 10^{17} cm^{-3} . The second well region **106** may be formed to be laterally disposed from the first well region **104**. In an alternative embodiment, the first well region **104** may be formed to laterally extend below the gate stack (which will be described in more detail below) to the second well region **106**.

In various embodiments, the remaining process flow may be similar to the as such standard CMOS process flow and will be described in more detail below.

FIG. 6 shows a cross sectional view **600** of a semiconductor device in accordance with an embodiment at a fourth stage of its manufacturing.

In various embodiments, as shown in FIG. 6, the second isolation layer **124** (e.g. a gate dielectric layer **124**) may be disposed (and suitably patterned) over an active region **114**. The second isolation layer **124** may include or consist of a dielectric material such as e.g. an oxide (e.g. silicon oxide), a nitride (e.g. silicon nitride) or an oxynitride (ON). In alternative embodiments, the second isolation layer **124** may include or consist of high k dielectric material (i.e. e.g. a material having a dielectric constant of greater than the dielectric constant of silicon oxide (which has a dielectric constant of 3.9)). In various implementations, the second isolation layer **124** may include or consist of may include or consist of aluminum oxide (Al_2O_3), yttrium oxide (Y_2O_3), hafnium oxide (HfO_2), lanthanum oxide (La_2O_3), zirconium oxide (ZrO_2), amorphous silicon (a-Si), tantalum oxide (Ta_2O_5), titanium oxide (TiO_2), and/or an aluminate. An example for an aluminate is an alloy of the components aluminum, zirconium and oxygen (AlZrO). In an implementation, the second isolation layer **124** may include or consist of a dielectric layer stack including three dielectric layers being formed above one another, e.g. a first oxide layer (e.g. silicon oxide), a nitride layer as charge trapping layer (e.g. silicon nitride) on the first oxide layer, and a second oxide layer (e.g. silicon oxide or aluminum oxide) on the nitride layer. This type of dielectric layer stack is also referred to as ONO layer stack. In an alternative implementation, the second isolation layer **124** may include or consist of two, four or even more dielectric layers being formed above one another. In some embodiments, the second isolation layer **124** may have a physical layer thickness in the range from about 1.5 nm to about 5 nm, e.g. a physical layer thickness in the range from about 2 nm to about 3 nm and/or an equivalent oxide thickness (EOT) in the range from about 1 nm to about 2 nm.

It is to be noted that in some embodiments, the liner layer **302** in the first trench **116** may be an implementation of the first isolation layer. Furthermore, in an option, the above described layer or layer structure that is deposited for the second isolation layer **124** may also be deposited on the bottom and the sidewalls of the first trench over the liner layer **302**. In this case, the liner layer **302** together with the additional layer structure may be an implementation of the first isolation layer.

FIG. 7 shows a cross sectional view **700** of a semiconductor device in accordance with an embodiment at a fifth stage of its manufacturing.

Then, a layer **702** made of electrically conductive material (such as e.g. polysilicon (doped or undoped) or a metal, e.g. tungsten or a silicide (e.g. WSi)) is deposited over the entire upper surface of the semiconductor device resulting from the fourth stage of its manufacturing, wherein also the first trench **116** may be completely filled and possible overfilled.

FIG. 8 shows a cross sectional view **800** of a semiconductor device in accordance with an embodiment at a sixth stage of its manufacturing.

Then, the layer **702** may be patterned to form the electrically conductive material **126** of the gate region to be formed as well as the electrically conductive material **128** filling the first trench **116**. In some embodiments, the electrically conductive material **126** of the gate region to be formed and the electrically conductive material **128** filling the first trench **116** may be physically and electrically coupled with each other. Furthermore, it should be mentioned that the patterning of the layer **702** should be carried out in such a way that the electrically conductive material of the patterned layer **702** does not touch (in other words is not in direct physical or electrical contact) with the upper surface of the semiconductor material of the substrate **102**, e.g. the silicon, in particular not with the upper surface of the semiconductor material of the substrate **102**, in which the source/drain regions **108**, **110** (e.g. the source region **108** or the drain region **110**) will later be formed.

FIG. 9 shows a cross sectional view **900** of a semiconductor device in accordance with an embodiment at a seventh stage of its manufacturing.

Next, as shown in FIG. 9, a lightly doped drain (LDD) ion implantation process may be carried out to form a lightly doped drain (LDD) implant region **902** which may include the lightly doped drain region **146**. Furthermore, electrically insulating material **904** (e.g. an oxide such as e.g. silicon oxide) may be deposited over the entire upper surface of the semiconductor device resulting from the sixth stage of its manufacturing, wherein the electrically insulating material **904** may be used to form the sidewall spacers **142**, **144**, as will be described in more detail below.

FIG. 10 shows a cross sectional view **1000** of a semiconductor device in accordance with an embodiment at an eighth stage of its manufacturing.

Then, the sidewall spacers **142**, **144** may be formed, e.g. by means of a spacer etch process, thereby exposing a portion of the upper surface of the lightly doped drain (LDD) implant region **902**, in which portion the first source/drain region **108** may be formed at a subsequent process, and a portion of the upper surface of the substrate **102**, in which portion the second first source/drain region **110** may be formed at a subsequent process.

FIG. 11 shows a cross sectional view **1100** of a semiconductor device in accordance with an embodiment at a ninth stage of its manufacturing.

Then, another ion implantation process is carried out to form the first source/drain region **108** (e.g. the source region **108**) and the second source/drain region **110** (e.g. the drain region **110**). The ion implantation process may be carried out in such a manner that the first source/drain region **108** and the second source/drain region **110** may be highly n-doped (n^+ doped) having a doping concentration in the range from about 10^{19} cm^{-3} to about 10^{21} cm^{-3} , e.g. with a doping concentration of doping atoms in the range from about $5 \cdot 10^{19} \text{ cm}^{-3}$ to about $5 \cdot 10^{20} \text{ cm}^{-3}$. In general, the first source/drain region **108** and the second source/drain region **110** may be doped with doping atoms of a first conductivity type, and the first well region **104** may be doped with doping atoms of a second conductivity type, wherein the second conductivity type is different from the first conductivity type.

In various embodiments, the first source/drain region **108** as well as the second source/drain region **110** may be formed such that they extend into the substrate **102** from the upper main processing surface **112** of the substrate **102** by a depth in the range from about 50 nm to about 200 nm, wherein the

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depth of the first source/drain region **108** and the depth of the second source/drain region **110** may be similar or different from each other. Furthermore, the external contacts may be formed (e.g. for the first source/drain region, the second source/drain region or the gate region) including e.g. a silici-

dation process. In various embodiments, the width of the first trench **116** and the thickness of the gate region may be parameters having influence of the characteristics of the semiconductor device **100**, e.g. having influence on the filling of the first trench **116** underneath the gate-to-drain overlap. In various embodi-

ments, the first trench **116** has a depth in the range from about 300 nm to about 400 nm and a width in the range from about 200 nm to about 1000 nm. FIG. **12** shows a diagram **1200** illustrating the On-resistance (R_{ON}) and the On-current (I_{ON}) dependent from the applied gate voltage (V_{GT}). As is shown in FIG. **12**, the semiconductor device **100** having illustratively the dual gate STI DeMOS structure (in other words, the first trench being at least partially filled with electrically conductive material and coupled to an external contact terminal) shows a 30% lower On-resistance (R_{ON}) compared with the conventional STI DeMOS device for the same dimensions.

FIG. **13** shows a diagram **1300** illustrating the On-resistance and the On-current dependent from the thickness of the insulating layer within the first trench of the semiconductor device **100** of FIG. **1**. As shown in FIG. **13**, semiconductor device **100** having illustratively the dual gate STI DeMOS structure (in other words, the first trench being at least partially filled with electrically conductive material and coupled to an external contact terminal) shows higher variability in the On-resistance (R_{ON}) compared with the conventional STI DeMOS device for the same dimensions.

FIG. **14** shows a cross sectional view of a semiconductor device **1400** in accordance with another embodiment. The semiconductor device **1400** of FIG. **14** is similar to the semiconductor device **100** of FIG. **1** with the main difference that in the semiconductor device **1400** of FIG. **14**, the second trench **148** is not completely filled with electrically insulating material such as an oxide (e.g. silicon oxide), but has another structure, which is similar to the structure of the first trench **116**. Illustratively, the second trench **148** in the semiconductor device **1400** of FIG. **14** is not a shallow trench isolation, but has an electrically insulating layer **1402** (which may be similar to the first isolation layer **118**) covering the bottom and the sidewalls of the second trench **148**, but may also be filled with electrically conductive material **1404**. Thus, the completed structure of the second trench **148** may be similar to the completed structure of the first trench **116** in accordance with this embodiment. Illustratively, in various embodiments, the second trench **148** may be filled with Metal or Pre-doped polysilicon (after the formation of a nitride liner, for example).

FIG. **15** shows a cross sectional view of a semiconductor device **1500** in accordance with yet another embodiment. The semiconductor device **1500** of FIG. **15** is similar to the semiconductor device **100** of FIG. **1** with the main difference that in the semiconductor device **1500** of FIG. **15**, the electrically conductive material of the gate region **126** is not directly physically coupled with the electrically conductive material **128** filling the first trench **116**, but they are physically (and electrically) isolated from each other by means of the second isolation layer **124**, the sidewall spacer **144** and the first isolation layer **118**. However, in various embodiments, the electrically conductive material **128** filling the first trench **116** may be coupled to an external contact terminal **1502** which in turn may be coupled to the gate region **126** for the application

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of an external voltage. Illustratively, the electrically conductive material **128** filling the first trench **116** and the gate region **126** may both be coupled to the external contact terminal **1502**, but in alternative embodiments, they may also be coupled to two separated external contact terminal for the application of external voltages. Thus, a structure having two separate gates that can be externally connected to each other or separately to two power (e.g. voltage) sources may be provided in various embodiments. One gate may be used to invert the channel region and the other gate may be used to improve the gate oxide breakdown in off-state of the semiconductor device and improve turn-on characteristics in on-state of the semiconductor device. The two gates may thus also be controlled separately and independently from each other.

In another embodiment, the above described features of the semiconductor device **1400** of FIG. **14** and of the semiconductor device **1500** of FIG. **15** may be combined (not shown in the figures).

In various embodiments, a semiconductor device may be processed in a dual gate process, where the one trench may be used as an isolation between devices (e.g. implemented as an STI) and the other trench in the N-Well underneath the drain edge of the gate region of a so-called drain extended high voltage device, may be used to form a U-shaped gate. The second gate may be constructed from an isolating layer and a conductive gate material both filling the trench. By applying a gate voltage, the drain region may be modified from accumulation to depletion changing the drain resistance of the semiconductor device.

In various embodiments, the existing conventional trench etching process and gate deposition process may be used. In some embodiments, the second gate formed underneath the gate-to-drain overlap region may protect against gate oxide breakdown and may improve hot carrier reliability in the off state. It may give an improved turn-on behaviour of the semiconductor device in accordance with various embodiments as compared to a conventional DeMOS processed semiconductor device in STI technology and may enhance the mixed signal performance.

In various embodiments, methods of forming a variation of a dual gate high voltage input/output (I/O) semiconductor device in sub 65 nm technology are provided.

In various embodiments, a novel way to improve mixed signal performance of a drain extended MOS (having an STI underneath gate-drain overlap) semiconductor device may be provided without degrading gate oxide reliability and hot carrier reliability.

In various embodiments, a semiconductor device is provided, which may include a first source/drain region, a second source/drain region, an active region electrically coupled between the first source/drain region and the second source/drain region, a drain extended structure disposed next to the second source/drain region, a trench disposed between the first source/drain region and the second source/drain region a first isolation layer disposed over the bottom and the sidewalls of the trench, electrically conductive material disposed over the isolation layer in the trench, and a gate structure disposed over the second isolation layer. The electrically conductive material may be coupled to an electrical contact configured to be coupled to a power source. In an implementation of these embodiments, the gate structure may include a gate isolation layer disposed over the active region, and a gate region disposed over the gate isolation layer. In another implementation of these embodiments, the power source is a voltage source. In yet another implementation of these embodiments, the semiconductor device may further include a first well region,

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wherein the first source/drain region may be disposed within the first well region. In yet another implementation of these embodiments, the first source/drain region may be doped with doping atoms of a first conductivity type, and the first well region may be doped with doping atoms of a second conductivity type, wherein the second conductivity type is different from the first conductivity type. In yet another implementation of these embodiments, the drain extended structure may include a second well region, wherein the second source/drain region may be disposed within the second well region. In yet another implementation of these embodiments, the second source/drain region may be doped with doping atoms of a first conductivity type, and the second well region may be doped with doping atoms of the first conductivity type. In yet another implementation of these embodiments, the semiconductor device may further include a lightly doped drain region disposed between the first source/drain region and the active region. In yet another implementation of these embodiments, the first isolation layer may include a material selected from a group of materials consisting of: silicon oxide; silicon nitride high-k material. In yet another implementation of these embodiments, the second isolation layer may include a material selected from a group of materials consisting of: silicon oxide; silicon nitride high-k material. In yet another implementation of these embodiments, the at least one of the first source/drain region and the second source/drain region may include silicide. In yet another implementation of these embodiments, the trench may be configured as a shallow trench isolation structure. In yet another implementation of these embodiments, the gate region may be electrically coupled with the electrically conductive material. In yet another implementation of these embodiments, the electrically conductive material may include a metal. In yet another implementation of these embodiments, the metal may be selected from a group of metals consisting of: tungsten, aluminum, copper or any silicide like NiSi, TiSi, CoSi. In yet another implementation of these embodiments, the semiconductor device may further include a further trench disposed next to the first source/drain region opposite to the active region. In yet another implementation of these embodiments, the further trench may be configured as a shallow trench isolation structure.

In various embodiments, a method for manufacturing a semiconductor device is provided. The method may include forming a first source/drain region, forming a second source/drain region, forming an active region between the first source/drain region and the second source/drain region, forming a drain extended structure next to the second source/drain region, forming a trench between the first source/drain region and the second source/drain region, forming a first isolation layer above the bottom and the sidewalls of the trench, forming electrically conductive material above the isolation layer in the trench, forming a gate structure above the second isolation layer, wherein the electrically conductive material is coupled to an electrical contact configured to be coupled to a power source. In an implementation of these embodiments, the forming of the gate structure may include forming a gate isolation layer above the active region, and forming a gate region above the gate isolation layer. In yet another implementation of these embodiments, the power source may be a voltage source. In yet another implementation of these embodiments, the method may further include forming a first well region, wherein the first source/drain region is formed within the first well region. In yet another implementation of these embodiments, the first source/drain region may be doped with doping atoms of a first conductivity type, and the first well region may be doped with doping atoms of a second

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conductivity type, wherein the second conductivity type is different from the first conductivity type. In yet another implementation of these embodiments, the drain extended structure may include a second well region, wherein the second source/drain region may be disposed within the second well region. In yet another implementation of these embodiments, the second source/drain region may be doped with doping atoms of a first conductivity type, and the second well region may be doped with doping atoms of the first conductivity type. In yet another implementation of these embodiments, the method may further include forming a lightly doped drain region between the first source/drain region and the active region. In yet another implementation of these embodiments, the first isolation layer may include a material selected from a group of materials consisting of: silicon oxide; silicon nitride high-k material. In yet another implementation of these embodiments, the second isolation layer may include a material selected from a group of materials consisting of: silicon oxide; silicon nitride high-k material. In yet another implementation of these embodiments, at least one of the first source/drain region and the second source/drain region may include silicide. In yet another implementation of these embodiments, the trench may be formed as a shallow trench isolation structure. In yet another implementation of these embodiments, the gate region may be electrically coupled with the electrically conductive material. In yet another implementation of these embodiments, the electrically conductive material may include a metal. In yet another implementation of these embodiments, the metal may be selected from a group of metals consisting of: tungsten, aluminum, copper or any silicide like NiSi, TiSi, CoSi. In yet another implementation of these embodiments, the method may further include forming a further trench next to the first source/drain region opposite to the active region. In yet another implementation of these embodiments, the further trench may be configured as a shallow trench isolation structure.

In various embodiments, a semiconductor device is provided. The semiconductor device may include a first source/drain region, a second source/drain region, an active region electrically coupled between the first source/drain region and the second source/drain region, a drain extended structure disposed next to the second source/drain region, a shallow trench isolation structure disposed between the first source/drain region and the second source/drain region, wherein the shallow trench isolation structure is partially filled with electrically conductive material, and a gate structure disposed over the active region. The electrically conductive material may be coupled to an electrical contact configured to be coupled to a power source. The coupling path can include a control circuit. In an implementation of these embodiments, the gate structure may include a gate isolation layer disposed over the active region, and a gate region disposed over the gate isolation layer. In yet another implementation of these embodiments, the power source is a voltage source. In yet another implementation of these embodiments, the semiconductor device may further include a first well region, wherein the first source/drain region may be disposed within the first well region. In yet another implementation of these embodiments, the first source/drain region may be doped with doping atoms of a first conductivity type, and the first well region may be doped with doping atoms of a second conductivity type, wherein the second conductivity type is different from the first conductivity type. In yet another implementation of these embodiments, the drain extended structure may include a second well region, wherein the second source/drain region may be disposed within the second well region. In yet another

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implementation of these embodiments, the second source/drain region may be doped with doping atoms of a first conductivity type, and the second well region may be doped with doping atoms of the first conductivity type. In yet another implementation of these embodiments, the semiconductor device may further include a lightly doped drain region disposed between the first source/drain region and the active region. In yet another implementation of these embodiments, the first isolation layer may include a material selected from a group of materials consisting of: silicon oxide; silicon nitride high-k material. In yet another implementation of these embodiments, the second isolation layer may include a material selected from a group of materials consisting of: silicon oxide; silicon nitride high-k material. In yet another implementation of these embodiments, at least one of the first source/drain region and the second source/drain region may include silicide. In yet another implementation of these embodiments, the gate region may be electrically coupled with the electrically conductive material. In yet another implementation of these embodiments, the electrically conductive material may include a metal. In yet another implementation of these embodiments, the metal may be selected from a group of metals consisting of: tungsten, aluminum, copper or any silicide like NiSi, TiSi, CoSi. In yet another implementation of these embodiments, the semiconductor device may further include a further trench disposed next to the first source/drain region opposite to the active region. In yet another implementation of these embodiments, the further trench may be configured as a shallow trench isolation structure.

While the invention has been particularly shown and described with reference to specific embodiments, it should be understood by those skilled in the art that various changes in form and detail may be made therein without departing from the spirit and scope of the invention as defined by the appended claims. The scope of the invention is thus indicated by the appended claims and all changes which come within the meaning and range of equivalency of the claims are therefore intended to be embraced.

What is claimed is:

1. A method for manufacturing a semiconductor device, the method comprising:

forming a first source/drain region within a first well region;

forming a second source/drain region within a second well region;

forming an active region electrically coupled between the first source/drain region and the second source/drain region, wherein the active region comprises a region of lower doping concentration disposed between the first well region and the second well region, wherein the region of lower doping concentration has a doping concentration lower than a doping concentration of each of the first well region and the second well region;

forming a trench disposed between the second source/drain region and at least a portion of the active region;

forming a first isolation layer on a bottom and sidewalls of the trench;

forming electrically conductive material in the trench, wherein the electrically conductive material is disposed over the first isolation layer;

forming a second isolation layer above the active region; and

forming a gate region above the second isolation layer; wherein the electrically conductive material is coupled to the gate region, and

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wherein the first well region is spaced apart from the second well region by the active region.

2. The method of claim 1, wherein the first source/drain region is doped with first doping atoms of a first conductivity type; and

wherein the first well region is doped with second doping atoms of a second conductivity type, wherein the second conductivity type is different from the first conductivity type.

3. The method of claim 1, wherein the second source/drain region is doped with doping atoms of a first conductivity type; and

wherein the second well region is doped with the doping atoms of the first conductivity type.

4. The method of claim 1,

wherein the trench is formed as a shallow trench isolation structure.

5. The method of claim 1, further comprising:

forming a lightly doped drain region disposed between the first source/drain region and the active region.

6. The method of claim 1, wherein the first isolation layer comprises a material selected from the group consisting of silicon oxide, silicon nitride and high-k material.

7. The method of claim 1, wherein the second isolation layer comprises a material selected from the group consisting of silicon oxide, silicon nitride and high-k material.

8. The method of claim 1,

wherein at least one of the first source/drain region and the second source/drain region comprises silicide.

9. The method of claim 1,

wherein the gate region is electrically coupled with the electrically conductive material.

10. The method of claim 1,

wherein the electrically conductive material comprises a metal.

11. The method of claim 1, wherein the metal is a material selected from the group consisting of tungsten, aluminum, copper and a silicide.

12. The method of claim 1, further comprising:

forming a further trench disposed next to the first source/drain region opposite to the active region.

13. The method of claim 12,

wherein the further trench is configured as a shallow trench isolation structure.

14. The method of claim 1, wherein forming the trench comprises forming the trench in a substrate, and

wherein forming the first isolation layer on the bottom and the sidewalls of the trench further comprising:

forming a liner layer over an entire exposed upper surface of the substrate, the bottom surface and the sidewall surfaces of the trench; and

removing first portions of the liner layer from the entire exposed upper surface of the substrate, wherein second portions of the liner layer covering the bottom surface and the sidewall surfaces of the trench remain.

15. The method of claim 14, wherein removing the first portions of the liner layer from the entire exposed upper surface of the substrate comprises a polishing process.

16. The method of claim 15,

wherein the polishing process comprises a chemical mechanical polishing (CMP) process.

17. The method of claim 14, wherein forming the gate region and forming the electrically conductive material in the trench further comprising:

depositing a layer of the electrically conductive material over the entire exposed upper surface of the substrate,

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wherein the trench is completely filled with the layer of the electrically conductive material; and
patterning the layer of the electrically conductive material to form the gate region and the electrically conductive material filling the trench.

18. A method for manufacturing a semiconductor device, the method comprising:

forming a first well region in the substrate;
forming a second well region in the substrate and spaced apart from the first well region;
forming a first source/drain region within a first well region;
forming a second source/drain region in the second well region;
forming a drain extended structure including a trench in the second well region and next to the second source/drain region;

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forming an active region electrically coupled between the first source/drain region and the second source/drain region, wherein the active region comprises a region of lower doping concentration than a doping concentration of each of the first well region and the second well region, and wherein the active region is disposed between the first well region and the second well region;
forming a first isolation layer on a bottom and sidewalls of the trench;
forming electrically conductive material in the trench, wherein the electrically conductive material is disposed over the first isolation layer;
forming a second isolation layer over the active region; and
forming a gate structure over the second isolation layer; wherein the electrically conductive material is coupled to the gate structure.

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